य कि	Application No.	Applicant(s)	
Notice of Allowability	10/053,160	HUANG ET AL.	
	Examin r	Art Unit	
	Lan Vinh	1765	
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED or other appropriate comr IGHTS. This application is	in this application. If not included nunication will be mailed in due cours	se. THIS he initiative
1. This communication is responsive to Amendment filed on	<u>11/10/2003</u> .		
2. The allowed claim(s) is/are 1-5 and 7-10.			
3. \boxtimes The drawings filed on <u>15 January 2002</u> are accepted by the			
 Acknowledgment is made of a claim for foreign priority ur a)	nder 35 U.S.C. § 119(a)-(d) or (f).	
 Certified copies of the priority documents have 	e been received.		
Certified copies of the priority documents have	e been received in Applicat	ion No. <u>10/053,160</u> .	
3. Copies of the certified copies of the priority do	cuments have been receiv	ed in this national stage application fr	om the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
 Acknowledgment is made of a claim for domestic priority un reference was included in the first sentence of the specifical 	nder 35 U.S.C. § 119(e) (to	o a provisional application) since a sp	ecific
(a) ☐ The translation of the foreign language provisional a			
Acknowledgment is made of a claim for domestic priority up in the first sentence of the specification or in an Application	nder 35 U.S.C. §§ 120 and	/or 121 since a specific reference wa	s included
Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT of	this communication to file this application. THIS TH	a reply complying with the requireme	ents noted ENDABLE.
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 	itted. Note the attached Exes reason(s) why the oath	(AMINER'S AMENDMENT or NOTIC or declaration is deficient.	E OF
8. CORRECTED DRAWINGS (as "replacement sheets") mus			
(a) including changes required by the Notice of Draftspers	son's Patent Drawing Revie	ew (PTO-948) attached	
1) hereto or 2) to Paper No			
(b) ☐ including changes required by the proposed drawing c			
(c) ☐ including changes required by the attached Examiner's	s Amendment / Comment	or in the Office action of Paper No	·
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on he margin according to 37 C	the drawings in the front (not the back) FR 1.121(d).) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT FOR T 	sit of BIOLOGICAL MATHE DEPOSIT OF BIOLOG	FERIAL must be submitted. Note t	he
Attachm nt(s)			
1☐ Notice of References Cited (PTO-892)	5∐ Notice of In	formal Patent Application (PTO-152)	
2☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6∐ Interview S	ummary (PTO-413), Paper No	. •
3 Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No	i), 7□ Examiner's	Amendment/Comment	
4☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examiner's 9⊡ Other	Statement of Reasons for Allowance	
	a Ottiei	•	
	-	Lan Vinh AU 1785	

U.S. Patent and Trademark Office PTOL-37 (Rev. 11-03)



Application/Control Number: 10/053,160

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Allowable Subject Matter

1. Claims 1-5, 7-10 are allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claims 1, 4, no cited prior art of record discloses a method for etching a mask layer comprises the step of forming a victim layer comprised of anti-reflection coating layer on the surface of the photoresist according to the photoresist topography, wherein the thickness of the victim layer is smaller than that of the photoresist, such that a plurality of slopes are formed on the sidewalls of the photoresist. The closest cited prior art of Schrems (US 6,040,211) discloses forming a photoresist layer over the anti-reflective coating layer that is formed over a hardmask (col 4, lines 40-43)

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Conclusion

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703 308-0661.

January 6, 2004